

SPUTTERING TARGET FOR MAGNETIC RECORDING MEDIA

ABSTRACT

Provided is a sputtering target for magnetic recording media
5 capable of producing a magnetic thin film in which the magnetic
crystal grains are micronized and the distance between the centers
of the magnetic crystal grains is reduced while good magnetic
properties are maintained.

A sputtering target for magnetic recording media comprising
10 metallic Pt and an oxide, with the balance being metallic Co and
inevitable impurities, wherein the metallic Co is contained in a
range of 70 at% or more and 90 at% or less and the metallic Pt is
contained in a range of 10 at% or more and 30 at% or less relative
to a total of metallic components in the sputtering target for magnetic
15 recording media, the oxide is contained in a range of 26 vol% or
more and 40 vol% or less relative to a total volume of the sputtering
target for magnetic recording media, and the oxide is composed of
 B_2O_3 and one or more high-melting-point oxides having a melting point
of 1470°C or higher and 2800°C or lower.

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[Figure 1]